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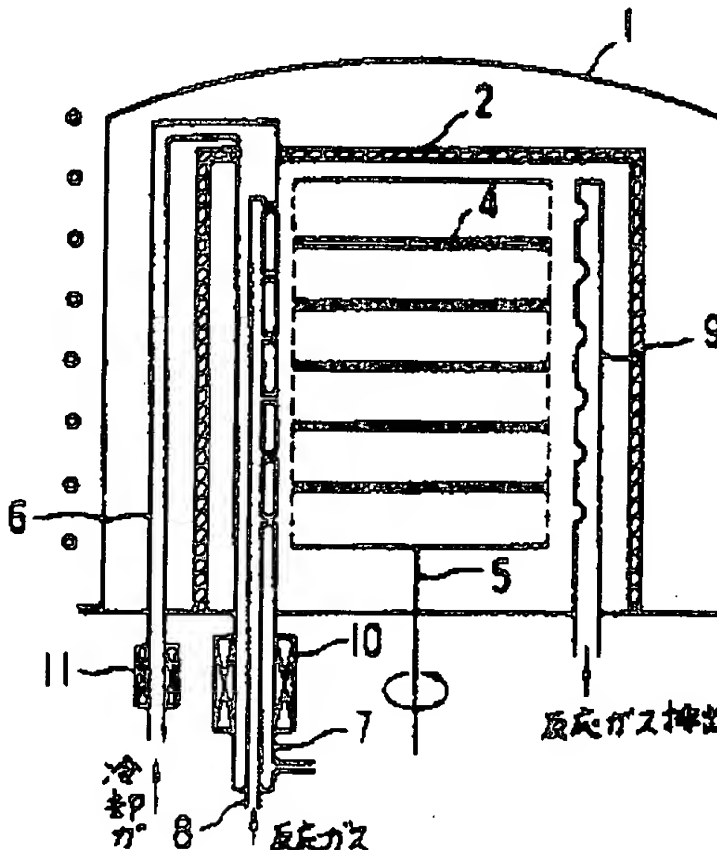
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(54) CVD DEVICE

(57) Abstract:

PURPOSE: To control the thickness of films on plural substrates with higher accuracy by providing a means to preheat reaction gas entering into a nozzle tube so as to make the distributed amount of flow at each hole of nozzles suitable.

CONSTITUTION: A multi-porous nozzle tube 8 and a construction of multiple-unit tubes through which reaction gas and cooling gas are flown. A preheating means 10 is provided to preheat the reaction gas to be supplied to the nozzle tube 8. Then, the reaction gas is injected into a substrate reaction chamber on each stage with the nozzle tube 8 through piping. The reaction gas is discharged through a suction pipe 9. Cooling gas is supplied through piping 6. The preheating temperature is controlled at a constant value with the preheating means 10, thereby providing suitable distribution



amount of flow at each holes of the nozzle, with highly accurately controlled thickness of films on plural substrates.

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